09/295607

Sheet 1 of 2

Form PTO-1449 (Rev. 8-83) U.S. Department of Commerce Patent and Trademark Office	Attorney Docket No. 0756-1961	Serial No. Not Yet Assigned
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)	Applicant: Shunpei YAMAZAKI et al.	
	Filing Date:	Group: 2812

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
Loke	4,727,044	2/23/88	Yamazaki			
Loke	4,959,700	9/25/90	Yamazaki			
Loke	5,142,344 8-25-1992	~~5/24/91~~	Yamazaki			
Loke	4,415,383	11/15/83	Naem et al.			
Loke	4,523,962	6/18/85	Nishimura			
Loke	4,431,459	2/14/84	Teng			
Loke	4,851,363	7/25/89	Troxel et al.			
Loke	4,959,700	9/25/90	Yamazaki			2/3/88
Loke	5,306,651	4/26/94	Masumo et al.	437	40	5/10/91
Loke	4,561,906	12/31/85	Calder et al.	437	101	10/24/83
Loke	5,091,334	2/25/92	Yamazaki et al.	437	101	6/29/81
Loke	5,272,361	12/21/93	Yamazaki	257	66	6/13/90

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	Document Number	Date	Country	Class	Subclass	Translation Yes	Translation No
Loke	59-121876	7/14/84	Japan			Abstract	
Loke	60-245174	12/4/85	Japan			Abstract	
Loke	6-59280	3/4/94	Japan			Abstract	
Loke	5-206468	8/13/93	Japan			Abstract	
Loke	1-187983	7/27/89	Japan			Abstract	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Loke		Sameshima et al., Japanese Journal of Applied Physics, "XeCl Excimer Laser Annealing Used to Fabricate Poly-Si TFT's", Vol. 28, No. 10, October, 1989, p. 1789-1793.
Loke		Sera et al., "High Performance TFT's Fabricated by XeCl Excimer Laser Annealing of Hydrogenated Amorphous Silicon Film", IEEE Transactions, 36 (1989), p. 2868-2872.

Examiner	Loke	Date Considered	7/29/99

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

The correction shown above is approved by S. Hu, on 05/08/2009

Form PTO-1449 (Rev. 8-83)	U.S. Department of Commerce Patent and Trademark Office	Attorney Docket No. 0756-1961	Serial No. 09/295,607
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		Applicant: Shunpei YAMAZAKI et al.	
		Filing Date: April 22, 1999	Group: 2811

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Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
Loke	5,147,826	09/15/92	Liu et al			
	5,275,851	01/04/94	Fonash et al			
	5,134,018	07/28/92	Tokunaga			
	4,057,895	11/15/77	Ghezzo			
	5,920,781	07/06/99	Imoto			
	4,599,118	07/08/86	Han et al			
	5,830,787	11/03/98	Kim			
	4,282,~~646~~ 543	08/04/81	Ihara et al			
	5,946,561	08/31/99	Yamazaki et al			
Loke	5,091,334	02/25/92	Yamazaki et al			

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	Document Number	Date	Country	Class	Subclass	Translation Yes	Translation No
Loke	EP 0 474 289 A1	03/11/92	Europe				
	63-258063	10/25/88	Japan			Abstract	
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Loke		Hempel et al., "Needle-Like Crystallization of Ni Doped Amorphous Silicon Thin Films", Solid State Communications, Vol. 85, No. 11, March 1993, pp. 921-924
		Hayzelden et al., "In Situ Transmission Electron Microscopy Studies of Silicide-Mediated Crystallization of Amorphous Silicon", Appl. Phys. Lett., Vol. 60, No. 2, January 13, 1992, pp. 225-227
		Dvurenchenskii et al., "Transport Phenomena in Amorphous Silicon Doped by Ion Implantation of 3d Metals", Phys. Stat. Sol. Vol. (a) 95, (1986), pp. 635-640
		Crowder et al., "DMOS FET with Common Field and Channel Doping", IBM Technical Disclosure Bulletin, Vol. 20, No. 4, September 1977, pp. 1617-1621
		Fathimulla et al., "Reactively rf Magnetron Sputtered AlN Films as Gate Dielectric", J. Appl. Phys., Vol. 54, No. 8, August 1983, pp. 4586-4589
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Examiner	Loke	Date Considered	9/28/00

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Submitted with IDS of September 5, 2000

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INFORMATION DISCLOSURE STATEMENT		Applicants: Shunpei YAMAZAKI et al.	
		Filing Date: April 22, 1999	Group Art Unit: 2811

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Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
Loke	2001/0050664	12/13/2001	Yamazaki et al.			
	4,468,855	09/04/1984	Sasaki			
	4,651,182	03/17/1987	Yamazaki			
	4,762,807	08/09/1988	Yamazaki			
	4,826,711	05/02/1989	Yamazaki et al.			
	5,313,077 05	~~03~~/17/1994	Yamazaki			
	5,315,132	05/24/1994	Yamazaki			
	5,409,982	04/25/1995	Imura et al.			
	5,514,879	05/07/1996	Yamazaki			
	5,536,575	07/16/1996	Imura et al.			
	5,543,636	08/06/1996	Yamazaki			
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	5,614,732	03/25/1997	Yamazaki			
	5,652,016	07/29/1997	Imura et al.			
	5,859,445	01/12/1999	Yamazaki			
	6,011,277	01/04/2000	Yamazaki			
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AE 4-20 09

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Loke	0 072 216	02/16/1983	EP			Full Eng	
	0 486 284	05/20/1992	EP			Full Eng	
	02-153896	06/13/1990	JP			Eng Abst	
	03-022540	01/30/1991	JP			Full Eng	
	04-085922	03/18/1992	JP			Eng Abst	
	04-133029	05/07/1992	JP			Eng Abst	
	04-186775	07/03/1992	JP			Eng Abst	
	04-190329	07/08/1992	JP			Eng Abst	
	58-023479	02/12/1983	JP			Eng Abst	
Loke	58-071663	04/28/1983	JP			Eng Abst	

Examiner	Loke	Date Considered	7/27/02

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